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Publisher Correction: Integrated photonic guided metalens based on a pseudo-graded index distribution

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This Article contains an error in Equation 5.

$$\tilde{n}_{\text{eff-TM-EMT}}^2(f) = f \cdot n_{\text{slab-TM}}^2 + (1 - f)\varepsilon_g + \frac{1}{3} \left[\frac{P}{\lambda}, \pi, f, (1 - f), (n_{\text{slab-TM}}^2 - \varepsilon_g) \right]^2$$

should read:

$$\tilde{n}_{\text{eff-TM-EMT}}^2(f) = f \cdot n_{\text{slab-TM}}^2 + (1 - f)\varepsilon_g + \frac{1}{3} \left[\frac{P}{\lambda} \pi f (1 - f) (n_{\text{slab-TM}}^2 - \varepsilon_g) \right]^2$$

In addition, this Article contains an error in the Methods.

“The electron-beam lithography process (VISTEC variable-shape VB6B) was optimized using 85 nm of negative tone resist from TOK (OEBR-CAN038) on top of 30 nm of silicon antireflective coating (SiARC) ISX412 and 130 nm of spin on carbon (SOC) HM8102.”

should read:

“The electron-beam lithography process (VISTEC variable-shape SB3054) was optimized using 85 nm of negative tone resist from TOK (OEBR-CAN038) on top of 30 nm of silicon antireflective coating (SiARC) ISX412 and 130 nm of spin on carbon (SOC) HM8102.”

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